## A New Oxygen-Insertion Reaction into Silicon-Silicon Bonds with Tertiary Amine Oxides

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We reported an oxidation reaction of organodisilanes with perbenzoic acid.<sup>1)</sup> Spialter and Austin subsequently described oxidative cleavage of the siliconsilicon bonds with oxides of nitrogen<sup>2)</sup> and ozone.<sup>3)</sup> These reagents are regarded as electrophilic and kinetic investigations led to the suggestion of a mechanism similar to that of epoxidation.<sup>1,3)</sup> We now wish to describe a new and mechanistically interesting insertion reaction of oxygen from tertiary amine oxides into silicon-silicon bonds. The reaction also constitutes a new reduction of amine oxides.<sup>4)</sup>

Trimethylamine N-oxide reacts exothermally with phenoxypentamethyldisilane in dimethyformamide (DMF), yielding phenoxypentamethyldisiloxane in a moderate yield.<sup>5)</sup> Oxidation of hexamethyldisilane to hexamethyldisiloxane with trimethylamine N-oxide required somewhat drastic conditions, the yield being 71% after heating at 90—100°C for 6 hr in DMF. Vinylpentamethyldisilane afforded vinylpentamethyldisiloxane in contrast to the reaction with perbenzoic acid.<sup>1)</sup>

Pyridine N-oxide reacts more slowly than does trimethylamine N-oxide. Treatment of phenoxypentamethyldisilane with pyridine N-oxide in DMF,

Table 1. Second Order rate constants for oxidation reaction of phenoxypentamethyldisilanes with pyridine N-oxide in toluene at  $135.0^{\circ}\mathrm{C}^{a}$ 

Substituent	$l^{10^5} k,^{b)} l  \mathrm{mol^{-1}  sec^{-1}}$	
p-CH <sub>3</sub> O	$6.43 \pm 0.27$	
$m$ -CH $_3$	$6.32 \pm 0.16$	
H	$9.74 \pm 0.50$	
<i>p</i> -Cl	$21.9 \pm 0.7$	
$m ext{-}\mathrm{CF}_3$	$38.7 \pm 2.4$	
$p ext{-}\mathrm{CH_3CO}$	$37.5 \pm 0.8$	

- a) Initial concentrations of silanes and pyrdine N-oxide were 0.02—0.21 mol  $l^{-1}$  and 0.03—0.3 mol  $l^{-1}$ , respectively.
- b) Average of two to four runs.

dioxane or toluene afforded phenoxypentamethyldisiloxane in over 85% yield. Although hexamethyl disilane did not react with pyridine N-oxide, other organodisilanes such as phenyl, 1,2-diphenyl-, and 1,1-diphenyl-substituted permethylated disilanes gave the corresponding disiloxanes as single products together with pyridine in dioxane.

$$\begin{array}{ccc} X-SiMe_2SiMe_3\,+\,C_5H_5NO\, &\longrightarrow \\ \\ X-SiMe_2OSiMe_3\,+\,C_5H_5N \end{array}$$

These results suggest a nucleophilic attack of N-oxides on the silicon-silicon bond as a primary step, which was supported by kinetic studies.

The extent of reaction of substituted phenoxypentamethyldisilane with pyridine N-oxide in toluene at 135.0°C was followed by the disappearance of disilanes (glpc), the second-order rate law being found to hold accurately. The results are listed in the Table.

A tolerably good Hammett plot was obtained between  $\log (k/k_{\rm H})$  and  $\sigma$  (r=0.971). A positive reaction constant  $\rho$  = +1.18 indicates nucleophilic attack of N-oxides at silicon to be involved in the rate-determining step.

The mechanism and rate parameters of the reaction appeared interesting in connection with the peracid oxidation of disilanes.<sup>1)</sup>

<sup>1)</sup> H. Sakurai, T. Imoto, N. Hayashi, and M. Kumada, J. Amer. Chem. Soc., 87, 4001 (1965).

<sup>2)</sup> L. Spialter and J. D. Austin, ibid., 88, 1828 (1966).

<sup>3)</sup> L. Spialter and J. D. Austin, Inorg. Chem., 5, 1975 (1966).

<sup>4)</sup> K. Naumann, G. Zon and K. Mislow, J. Amer. Chem. Soc., 91, 2788, 7012 (1969), reported the use of hexachlorodisilane as a reducing agent for phosphine oxides, amine oxides, and sulfoxides. They suggested the intermediacy of hexachlorodisiloxane formed by a mechanism involving a free trichlorosilyl anion. In the present study, however, it has been disclosed that organodisilanes are generally capable of reducing amine oxides.

<sup>5)</sup> Yields of disiloxane depend on the degree of dehydration of Me<sub>3</sub>NO·2H<sub>2</sub>O. Main by-products were phenol and (Me<sub>3</sub>-SiMe<sub>2</sub>Si)<sub>2</sub>O through hydrolysis.